IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Chiu, et al.

Attorney Docket: TSM02-1300

Filed:

Herewith

Examiner:

TBD

Serial No.:

TBD

Art Unit:

TBD

For:

Process for Patterning High-k Dielectric Material

Mail Stop: Patent Application Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Applicants wish to bring to the attention of the Patent and Trademark Office the information noted on the enclosed form PTO-1449 that may be considered material to the examination of the above identified application.

No fee is due at this time, as this Information Disclosure Statement is being filed concurrently with the patent application.

If the Examiner should have any questions, Applicants request that the Examiner contact Applicants' attorney at the number listed below.

Respectfully submitted,

Barry W. Dove

Attorney for Applicant

Reg. No. 45,862

Slater & Matsil, L.L.P. 17950 Preston Rd., Suite 1000 Dallas, TX 75252 (972) 732-1001 (phone) (972) 732-9218 (fax)

Approved for use through 10/31/2002. OMB 0651-0031

U.S. Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE
Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it displays a valid OMB

control number.

Substitu	ite for form 1449B	/PTO	,	Complet if Known		
				Application Number	TBD	
IN.	FORMATION	N DISCLO	SURE	Filing Date	Herewith	
8	TATEMENT			First Named Inventor	Chiu et al.	
(use as many sheets as necessary)				Group Art Unit	TBD	
				Examiner Name	TBD	
Sheet	1	of	1	Attorney Docket Number	TSM02-1300	

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS

Examiner nitials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the citem (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.						
	1	WOLF, S., "Silicon Processing for the VLSI Era," Volume 4: Deep Submicron Process Technology, Lattice Press, Sunset Beach, CA, 2002, pp. 145-180.						
		,						
			-					
•								

Examiner	Date	
Signature	 Considered	100
		<u> </u>

Burden Hour Statement: This form is estimated to take 2.0 hours to complete. Time will vary depending upon the needs of the individual case. Any comments on the amount of time you are required to complete this form should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Assistant Commissioner for Patents, Washington, DC 20231*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line

Patents, Washington, DC 20231*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. 'Applicant's unique citation designation number (optional). 'Applicant is to place a check mark here if English language Translation is attached. This collection of information is required by 37 CFR 1.98. The information is required to obtain or retain a benefit by the public which is to file (and by the USPTO to process) an application. Confidentiality is governed by 35 U.S.C. 122 and 37 CFR 1.14. This collection is estimated tot ake 120 minutes to complete, including gathering, preparing, and submitting the completed application form to the USPTO. Time will vary depnding upon the individual case. Any comments on the amount of time you require to complete this form and/or suggestions for reducing this burden should be sent to the Chief Information Officer, U.S. Patent and Trademark Office, Washington, DC 20231. DO NOT SEND FEES OR COMPLETED FORMS TO THIS ADDRESS. SEND TO: Commissioner for Patents, P. O. Box 1450, Alexandria, VA 22313-1450.

^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

¹Applicant's unique citation designation number (optional). ²Applicant is to place a check mark here if English language Translation is attached.